

IN THE CLAIMS

1 (Currently Amended). A method comprising:

 forming a photoresist using a photoacid generator having a first ring including
 iodine or sulfur and an aromatic ring ⁽¹⁾ and an anion selected from the group of ClO₄, SbF₆, and
perfluoroalkyl sulfonate. ⁽²⁾ ⁽³⁾

2 (Original). The method of claim 1 including forming said first ring as a sigma-bonded
ring.

3 (Original). The method of claim 1 including forming an aromatic ring as a phenyl
group.

4 (Original). The method of claim 1 including forming a napthyl ring structure.

5 (Original). The method of claim 1 including bonding said first ring directly to said
aromatic ring to form a napthyl ring.

Claims 6-10 (Canceled).

11 (Currently Amended). A photoresist comprising:

 a photoacid generator including a first ring and an aromatic ring directly bonded
 to said first ring; and

 said first ring including two atoms selected from the group including iodine and
 sulfur; and

an anion selected from the group of ClO₄, SbF₆, and perfluoroalkyl sulfonate.

12 (Original). The photoresist of claim 11 wherein said first ring is sigma-bonded.

13 (Original). The photoresist of claim 11 including two aromatic rings bonded to said
first ring.

14 (Original). The photoresist of claim 13 wherein said aromatic rings are bonded on opposite sides of said first ring.

15 (Original). The photoresist of claim 6 wherein said aromatic ring is a phenyl group.

16 (Original). The photoresist of claim 11 wherein said aromatic ring has an alkyl, phenyl, or caged alkyl attached to said ring.

Claim 17 (Canceled).